

*Amendment to the Specification*

Please change the title as follows:

~~Projection~~ Optical System for Maskless Lithography

Please modify the following paragraph to read as shown.

[0009] FIG. 1 shows a conventional SLM-based writing system 100 using a flat SLM 102 as a pattern generator. Light from illumination system 104 is directed to SLM 102 via a beam splitter 106 and an optical system (not shown) that contains at least an optical element 108. After reflecting from SLM ~~102~~ 104, light is passed through beam splitter 106 and directed to a substrate 110 via an optical system (not shown) having at least an optical element 112. In order to maintain a double telecentric beam towards SLM ~~102~~ 104 and substrate 110, optical element 108 must have a same diameter as SLM ~~102~~ 104. Beams can be considered double telecentric when a chief ray of each beam is parallel to an optical axis of the SLM ~~102~~ 104 and/or parallel to an optical axis of the substrate 110. There are manufacturing limits as to how large a diameter optical element 108 can have (e.g., 300-350 mm). This, in turn, limits a size of SLM ~~102~~ 104. Throughput is based on the size of SLM ~~102~~ 104. Thus, by restricting the size of SLM ~~102~~ 104 because of optical element 108, throughput is much lower than what could be obtained if a diameter of SLM ~~102~~ 104 was increased.